AMENDMENTS TO THE CLAIMS

1. (Previously Presented) A method of preparing a phosphor screen having at least a substrate and a phosphor layer comprising a $CsX:Eu^{2+}$ phosphor wherein X represents a halide selected from a group consisting of Br and Cl, wherein said phosphor is deposited by physical vapour deposition on said substrate, wherein during deposition said substrate is at a temperature in the range of 135°C to 235°C and wherein a variation of the temperature of the substrate occurring during said deposition process is not more than 50°C.

2. (Currently Amended) The [[A]] method according to claim 1 wherein said variation of the temperature of the substrate is not more than 30°C.

3. (Currently Amended) The [[A]] method according to claim 1 wherein said variation of the temperature of the substrate is not more than 20°C.

4. (Currently Amended) The [[A]] method according to claim 1 wherein said phosphor layer is deposited at a temperature in the range of 150°C to 220°C.

5. (Currently Amended) The [[A]] method according to claim 4 wherein said variation of the temperature of the substrate is not more than 30° C.

6. (Currently Amended) The [[A]] method according to claim 4 wherein said variation of the temperature of the substrate is not more than 20° C.

7. (Currently Amended) The [[A]] method according to claim 1 wherein said phosphor layer is deposited at a temperature in the range of 170°C-200°C and wherein said variation of the temperature of the substrate is not more than 20° C.

8. (Withdrawn) A phosphor screen prepared according to claim 1.

This listing of claims replaces all prior versions, and listings, of claims in the application.